

Spin Coater SCR

- Rotational speed up to 6.000 rpm
- Active vacuum suction of the sample
- OLED display
- Newly developed control electronics
- Film thickness range 10 nm to 10 μ m
- Easy-to-use and maintenance free design
- Single-knob setup with colored status LED
- Rotational platforms for substrates up to 50 mm diameter
- Standard stuck (30 mm diameter) included
- Built-in short fixed ramp
- Speed selection between 5 rps and 100 rps (300 rpm and 6000 rpm)
- Selected speed value stored in non-volatile memory, immediately available after repowering

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Novocontrol Technologies GmbH & Co. KG Aubachstr. 1 56410 Montabaur Germany





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The SCR spin coater helps you prepare thin films easily within a few minutes. Films are produced on a substrate that is fixed to an exchangable rotational platform by a pump-generated underpressure. Both circular and rectangular substrates up to 50 mm diameter can be placed on the rotational platform (various sizes available, see the accessories list).

The resulting film thickness merely depends on the solid/solvent concentration, rotational speed, and time.



The ergonomic design makes the SCR spin coater an efficient tool for the preparation of thin films of organic and inorganic substances for microscopic or spectroscopic investigations.

The SCR spin coater comes with a short fixed ramp. Rotational speeds can be selected from 5 rps to 100 rps (300 rpm to 6000 rpm). The last rotational speed set is stored in a non-volatile memory and thus is immediately available after the next powering up.

During operation, a built-in digital OLED display informs about the current rotational speed in rotations per second (rps).

Operating the SCR spin coaters is as easy as selectring a rotational speed by turning a single digital encoder knob and pressing the same to start spinning. The integrated LED indicates the device status through different colors.

Materials used are anodized aluminium for the housing, stainless steel for the top and PTFE for the detachable protection cover.

SCR Spin Coater

As a high quality product, the SCR spin coater comes with a two-year guarantee.

Accessories for the SCR spin coater

- Vacuum pump MVP with hose and quick coupling (highly recommended)
- VT-25p: rotational platform (plane chuck; Ø 25 mm, for small and irregularly shaped subtrates)
- VT-25pr6: VT-25p with inserted O-ring 6x1
- VT-25pr20: VT-25p with inserted O-ring 20x1
- VT-25pr: VT-25p with inserted O-rings 6x1 and 20x1
- VT-30 rotational platform (Ø 30 mm)
- VT-50 rotational platform (Ø 50 mm)

All rotational platforms are made of aluminium. Regular platforms are equipped with small channels on their surface to ensure uniform pressure on the substrate.

Plane platforms lack these channels; evacuation is performed exclusively through the center hole. This arrangement is better suited for small or irregularly shaped substrates that would leave major parts of the channel structure uncovered. The SCR spin coater comes with a switching power supply and a VT-30 rotational platform.



Small Vaccum Pump MVP

- Underpressure of -33,3 kPa
- Flow of 7 litres/min
- Max. 40 dB(A) noise
- Quick coupling of the vacuum hose



SCE-150 Spin Coater

- Rotational speed up to 9.000 rpm
- Rotational speed ramp function
- Programmable ramp duration: 3 s .. 600 s
- Programmable dwell time: 3 s .. 600 s
- Alphanumeric four-line display (20 characters/line)
- Settings stored in non-volatile memory
- Display of remaining processing time
- Total process times: 6 s .. 20 minutes
- Active vacuum suction of the sample
- Film thickness range 10 nm to 10 μm
- Easy-to-use and maintenance free design
- Rotational platforms for substrates up to 90 mm diameter





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Our SCE-150 spin coater with ramp function help you prepare thin films easily within a few minutes. Films are produced on a substrate that is fixed to an exchangable rotational platform by a pump-generated underpressure.

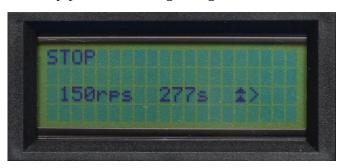
Both circular and rectangular substrates up to 90 mm diameter can be placed on the rotational platform (various sizes available, see the accessories list).

The resulting film thickness merely depends on the solid/solvent concentration, rotational speed, and time.

The ergonomic design makes the SCE-150 spin coater an efficient tool for the preparation of thin films of organic and inorganic substances for microscopic or spectroscopic investigations.

Spin coating using the SCE-150 spin coater neither requires specific skills nor prior experience and is maintenance free.

Operating and setting up the SCE-150 spin coater is easily performed using a single-know control.



During operation, a built-in digital LC display with 20 characters per line informs about the rotation speed and the remaining ramp or dwell times for testing under reproducible conditions. It also substantially facilititates the set-up of the spin coater. For the sake of reproducibility, the set-up is stored permanently in the SCE-150 nonvolatile memory.

The ramp and dwell times may be varied over a wide range, i.e., between 3 s and 600 s, total process times between 6 s and 10 minutes.

Using the SCE-150 spin coater, thin and ultra thin layers of extraordinary homogeneity are easily achieved.

As a high quality product, these spin coater come with 2 years guarantee.

Accessories for the SCE-150 spin coater

- Vacuum pump MVP with hose and quick coupling (highly recommended)
- VT-25p: rotational platform (plane chuck; Ø 25 mm, for small and irregularly shaped subtrates)
- VT-25pr6: VT-25p with inserted O-ring 6x1
- VT-25pr20: VT-25p with inserted O-ring 20x1
- VT-25pr: VT-25p with inserted O-rings 6x1 and 20x1
- VT-30: rotational platform (Ø 30 mm)
- VT-50: rotational platform (Ø 50 mm)
- VT-70: rotational platform (Ø 70 mm)
- VT-90: rotational platform (Ø 90 mm)

All rotational platforms are made of aluminium. Regular platforms are equipped with small channels on their surface to ensure uniform pressure on the substrate.

Plane platforms lack these channels; evacuation is performed exclusively through the center hole. This arrangement is better suited for small or irregularly shaped substrates that would leave major parts of the channel structure uncovered. The SCE-150 spin coater comes with a switching power supply and a VT-30 rotational platform.



Small Vaccum Pump MVP

- Underpressure of -33,3 kPa
- Flow of 7 litres/min
- Max. 40 dB(A) noise
- Exact appearance may vary.



Microprocessor-Controlled Spin Coater SCC-200

- Rotational speed up to 12.000 rpm
- Two rotational speed ramps
- Programmable ramp duration: 3 s .. 600 s
- Two rotational speed target values
- Programmable dwell time: 3 s .. 600 s
- Alphanumeric four-line display (20 characters/line)
- 10 rotational speed sequences storable in non-volatile memory
- Display of remaining processing time
- Total process times: 12 s .. 40 minutes
- Active vacuum suction of the sample
- Film thickness range 10 nm to 10 μm
- Easy-to-use and maintenance free design
- Rotational platforms for substrates up to 90 mm diameter

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Our microprocessor-controlled spin coater SCC-200 helps you prepare thin films easily within a few minutes. Films are produced on a substrate that is fixed to an exchangable rotational platform by a pump-generated underpressure.

Both circular and rectangular substrates up to 90 mm diameter can be placed on the rotational platform (various sizes available, see the accessories list).

The resulting film thickness merely depends on the solid/solvent concentration, rotational speed, and time.

The ergonomic design makes the SCC-200 spin coaters an efficient tool for the preparation of thin films of both organic and inorganic substances for



microscopic or spectroscopic investigations. Spin coating using the SCC-200 neither requires specific skills nor prior experience and is maintenance free.

During operation, a built-in digital four-line display with 20 characters per line informs about the rotation speed and the remaining ramp or dwell times for testing under reproducible conditions. It also substantially facilititates the set-up of the spin coater. For the sake of reproducibility, 10 programming sequences can be stored permanently in the SCC-200 non-volatile memory. These programmes consist of two rotational speeds up to 200 rps (12.000 rpm), ramp times, and dwell times, respectively. The latter may be varied over a wide range, i.e., between 3 s and 600 s, providing substantial flexibility to the spin coating process with total process times between 12 s and 40 minutes.

Operating and setting up the SCC-200 is easily performed by single-knob control.

Using the SCC-200, thin and ultra thin layers of extraordinary homogeneity are easily achieved.

As a high quality product, this spin coater comes with 2 years guarantee.

Accessories for the SCC-200

- Vacuum pump MVP with hose and quick coupling (highly recommended)
- VT-25p: rotational platform (plane chuck; Ø 25 mm, for small and irregularly shaped subtrates)
- VT-25pr6: VT-25p with inserted O-ring 6x1
- VT-25pr20: VT-25p with inserted O-ring 20x1
- VT-25pr: VT-25p with inserted O-rings 6x1 and 20x1
- VT-30: rotational platform (Ø 30 mm)
- VT-50: rotational platform (Ø 50 mm)
- VT-70: rotational platform (Ø 70 mm)
- VT-90: rotational platform (Ø 90 mm)

All rotational platforms are made of aluminium. Regular platforms are equipped with small channels on their surface to ensure uniform pressure on the substrate.

Plane platforms lack these channels; evacuation is performed exclusively through the center hole. This arrangement is better suited for small or irregularly shaped substrates that would leave major parts of the channel structure uncovered.

The SCC-200 comes with a switching power supply and a VT-30 rotational platform.



Small Vaccum Pump MVP

- Underpressure of -33,3 kPa
- Flow of 7 litres/min
- Max. 40 dB(A) noise
- Note: exact appearance may vary.



SCI-225 Spin Coater

- Rotational speed from 300 rpm to 13.500 rpm
- Efficient speed control to +/- 1rps
- OLED display (font colour white) with large reading angle
- "Passive" vacuum suction of the samples at higher speeds
- Non-volatile storage of the last selected speed
- Film thickness range 10 nm to 10 μm
- Easy-to-use and maintenance free design
- Rotational platforms for substrates up to 38 mm diameter
- Small dimensions, well suited for use within glove boxes
- Dimensions only 118mm x 69mm (diameter x height) with 13mm protrusion for the control knob
- All-metal housing with stainless steel bowl and PTFE cover
- External plug-in power supply
- Energy-efficient operation thanks to the use of state-of-theart components
- Attractive price/performance ratio





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The SCI-225 spin coater helps you prepare thin films easily within a few minutes. Films are produced on a substrate that is fixed to an exchangable rotational platform. The SCI-225 spin coater does not require a separate pump—instead, it uses a *passive* vacuum that is created by the rotation of the particularly designed chucks. These chucks feature radial channels, connecting the volume beneath the substrate and the outer rim of the chuck. Chucks have to fit more or less exactly into the usually circular cutout of the chuck in order to stay there during spin-up.

Both circular and rectangular substrates up to 38 mm diameter can be placed on the rotational platform (various sizes available, see the accessories list).

The resulting film thickness merely depends on the solid/solvent concentration, rotational speed, and time.

The ergonomic design makes the SCI-225 spin coater an efficient tool for the preparation of thin films of organic and inorganic substances for microscopic or spectroscopic investigations.

Spin coating using the SCI-225 spin coater neither requires specific skills nor prior experience and is maintenance free.

During operation, a built-in digital OLED display informs about the current rotational speed (in rotations per second).

Operating the SCI-225 spin coater is as easy as selectring a rotational speed by turning a single

SCI-225 Spin Coater

potentiometer and pressing the start button. Using the SCI-225 spin coater, thin and ultra thin layers of extraordinary homogeneity are easily achieved.

Dimensions: 118 mm Ø, 69 mm height with 13 mm protrusion for the control knob.

Accessories for the SCI-225

Rotational platforms are made of aluminium (ST 20) or stainless steel (VA)

For the SCI-225, the sample substrate size has to match the rotational platform inner diameter. Rotational platforms have to be ordered separately and are available with customized inner diameters between 10 mm to 38 mm; please specify upon ordering.

The SCI-225 spin coater is delivered with a switching power supply (voltage input from 100 V to 240 V) and an ST 20 rotational platform ("chuck") for substrates of 10 mm diameter.

Chuck	OD/mm	ID/mm
ST 20	20	10
ST 20 K	20	customized 10 19
ST 40	40	20
ST 40 K	40	customized 20 38

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GmbH & Co. KG Aubachstr. 1

56410 Montabaur

Germany